

AMENDMENTS TO THE CLAIMS:

This listing of claims replaces all prior versions and listings of claims in the application:

LISTING OF CLAIMS:

1. (Currently Amended) A method ~~for the manufacture of a device that includes the following steps comprising:~~

forming [[(1)]] a first electrode and a second electrode on a base body; and with two external electrodes opposite each other,

chemically etching at least a portion of the base body to adjust (b) Adjustment of the a resistance of the base body (1)-measured between the external electrodes first electrode and the second electrode. to a given target value by means of chemical etching of portions of the base body.

2. (Currently Amended) The method ~~according to Claim of claim 1~~, wherein [[a]] the base body (1) is utilized, which contains comprises a ceramic material.

3. (Currently Amended) The method ~~according to Claims 1 or 2 of claim 1~~, wherein the [[a]] base body (1) is utilized, whose ohmic comprises a material having a resistance [[has]] with a negative temperature coefficient.

4. (Currently Amended) The method ~~according to Claims 1 through 3 of claim 1,~~
wherein [[a]] a length of an edge of the base body (1) is utilized whose smallest dimension (d) is
less than about 3 mm.

5. (Currently Amended) The method ~~according to Claims 1 through 4 of claim 1,~~
wherein chemically etching at least a portion of the base body ~~the etching is carried out by~~
comprises immersing dipping the base body in an etching liquid. (1) into a liquid that etches the
base body (1).

6. (Currently Amended) The method ~~according to Claim of claim 5,~~ wherein the
etching liquid comprises sulfuric acid is used as etching liquid.

7. (Currently Amended) The method ~~according to one of Claims 1 through 6, of~~
claim 1, further comprising measuring a ~~wherein the actual value of [[the]]~~ a resistance of the
base body (1) is measured before step (b) prior to chemically etching the at least a portion of the
base body.

8. (Currently Amended) The method ~~according to Claim 7 of claim 1, further~~
comprising measuring a ~~wherein during the etching the resistance (R25) of the base body is~~
~~measured~~ while chemically etching the at least a portion of the base body.

9. (Currently Amended) The method ~~according to Claims 1 through 8~~ of claim 1,
further comprising:

determining a ~~wherein before step (b) the~~ difference between the ~~target~~ predetermined
value and ~~the actual~~ a measured value of the resistance; and

determining (R25) is determined, whereas a duration $[(t)]$ for the chemically etching
~~etch process is determined from~~ based on said difference, ~~and~~ wherein chemically etching at
least a portion of the base body comprises chemically etching at least a portion of the base body
~~in step (b) the base body (1) is etched for the so determined etch duration $[(t)]$.~~

10. (New) The method of claim 1, wherein forming the first electrode and the second
electrode on the base body comprises forming the first electrode at a location opposite the second
electrode on the base body.

11. (New) The method of claim 1, wherein chemically etching at least a portion of the
base body to adjust the resistance of the base body comprises chemically etching at least a
portion of the base body to adjust the resistance of the base body to a predetermined value.